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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/815,911	03/31/2004	Giuseppe Curello	42P18251	9311	
8791	7590 11/29/2005		EXAM	EXAMINER	
	SOKOLOFF TAYLO	CHAUDHARI, CHANDRA P			
12400 WILSH SEVENTH FI	HIRE BOULEVARD		ART UNIT	PAPER NUMBER	
	ES, CA 90025-1030		2891		

DATE MAILED: 11/29/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	4.			
Office Action Summary		10/815,911	CURELLO ET AL.				
		Examiner	Art Unit				
		Chandra Chaudhari	2891				
Period fo	The MAILING DATE of this communication app or Reply	ears on the cover sheet with the c	correspondence address				
WHIC - Exte after - If NC - Failu Any (ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DAYS OF THE MAILING DAYS OF THE MONTHS FROM THE MONTHS FROM THE MONTHS ATTEMPT OF THE MONTHS AFTER THE MAILING DAYS OF THE MONTHS AFTER THE T	ATE OF THIS COMMUNICATION 16(a). In no event, however, may a reply be time The state of the st	N. nely filed the mailing date of this communicati D (35 U.S.C. § 133).				
Status							
1)⊠	Responsive to communication(s) filed on 12 Se	eptember 2005.					
2a) <u></u> □	This action is FINAL . 2b)⊠ This	action is non-final.					
3)	Since this application is in condition for allowar	nce except for formal matters, pro	secution as to the merits	is			
	closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	53 O.G. 213.				
Dispositi	on of Claims						
4)⊠	Claim(s) <u>1-34</u> is/are pending in the application.						
4a) Of the above claim(s) <u>24-34</u> is/are withdrawn from consideration.							
5)	5) Claim(s) is/are allowed.						
=	6)⊠ Claim(s) <u>1-23</u> is/are rejected.						
	Claim(s) is/are objected to.						
8)□	Claim(s) are subject to restriction and/or	election requirement.					
Applicati	on Papers						
9)[The specification is objected to by the Examine	r.					
10)⊠	The drawing(s) filed on <u>31 March 2004</u> is/are: a	a)☐ accepted or b)⊠ objected to	by the Examiner.				
	Applicant may not request that any objection to the	drawing(s) be held in abeyance. See	e 37 CFR 1.85(a).				
	Replacement drawing sheet(s) including the correcti			(d).			
11)	The oath or declaration is objected to by the Ex	aminer. Note the attached Office	Action or form PTO-152.				
Priority u	ınder 35 U.S.C. § 119						
•	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a)	-(d) or (f).				
a) _l	☐ All b) ☐ Some * c) ☐ None of: 1. ☐ Certified copies of the priority documents	: have been received					
	2. Certified copies of the priority documents		on No				
	3. Copies of the certified copies of the prior	• •					
	application from the International Bureau	•	a iii tiilo Mational Otago				
* 5	See the attached detailed Office action for a list	` ''	d.				
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Attachmen		. 🗖					
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)	4) ∐ Interview Summary Paper No(s)/Mail Da					
3) 🔯 Inform	nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date 4-23-04, 9-12-05.		atent Application (PTO-152)				
J.S. Patent and T	rademark Office						

Applicant's election of claims 1-23 in the reply filed on September 12, 2005 is acknowledged.

Because applicant did not distinctly and specifically point out the supposed errors in the restriction

requirement, the election has been treated as an election without traverse (MPEP § 818.03(a)).

Figures 1-2 should be designated by a legend such as -- Prior Art-- because only that which is

old is illustrated. See MPEP § 608.02(g). Corrected drawings in compliance with 37 CFR 1.121(d)

are required in reply to the Office action to avoid abandonment of the application. The replacement

sheet(s) should be labeled "Replacement Sheet" in the page header (as per 37 CFR 1.84(c)) so as not

to obstruct any portion of the drawing figures. If the changes are not accepted by the examiner, the

applicant will be notified and informed of any required corrective action in the next Office action. The

objection to the drawings will not be held in abeyance.

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis

for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this

country, more than one year prior to the date of application for patent in the United States.

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the

United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by

another filed in the United States before the invention by the applicant for patent, except that an international application

filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application

filed in the United States only if the international application designated the United States and was published under

Article 21(2) of such treaty in the English language.

Art Unit: 2891

Claims 12-14, 18-23 are rejected under 35 U.S.C. 102(b) as being anticipated by the article by Ito – "Mechanical Stress Effect of Etch-Stop Nitride ... Design".

Ito (Figs. 1, 4-5, 13-14, Table 1 and pages 247-248) discloses the claimed invention by making a semiconductor device with trench isolation, a tensile inducing layer of silicon nitride wherein the layer introduces a tensile stress with thickness and stress as claimed.

Claims 12-14, 18-23 are rejected under 35 U.S.C. 102(b) as being anticipated by the article by Shimizu – "Local Mechanical-Stress Control ... Enhancement".

Shimizu (Figs. 1-4, Table 1, and pages 433-434) discloses the claimed invention by making a semiconductor device with trench isolation, a tensile inducing layer of silicon nitride with thickness and stress as claimed.

Claims 1-23 are rejected under 35 U.S.C. 102(b) as being anticipated by the article by Ito – "Effect of mechanical stress induced by etch-stop nitride ... performance".

Ito (Figs. 1, 3, 11-14, Table 1, and text) discloses the claimed invention by making a semiconductor device with trench isolation, a gate stack, implanting to form source and drain regions, contacts, a silicide layer formed prior to a tensile stress inducing layer of silicon nitride with thickness and stress as claimed.

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Art Unit: 2891

Claims 12-14, 18-20, 23 are rejected under 35 U.S.C. 102(e) as being anticipated by Toda – US 2005/0032275.

Toda (Fig. 14 and text in paragraphs 66-67) discloses the claimed invention by creating tensile stress in a silicon substrate 1 by creating STI 2, and tensile inducing layer of silicon nitride 7a.

Claims 1-8, 11-20, 23 are rejected under 35 U.S.C. 102(e) as being anticipated by Yeo – US 2004/0212035.

Yeo (Fig. 6b and text in paragraphs 58-63) discloses the claimed invention by making a semiconductor device with implanted source and drain regions, trench isolation 220, a gate stack, a tensile stress inducing layer of silicon nitride 260 with a silicide layer over the source and drain and the gate stack.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Art Unit: 2891

Claims 1-11, 15-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over (Ito or Shimizu) and applicant's admitted prior art.

(Ito or Shimizu) is applied as above and does not disclose creating contacts to the source and drain regions, and the gate stack nor implanting to create the source and drain regions. Applicant's admitted prior art on pages 1, 5-6 teaches that metal lines are provided to the source and drain regions and the gate to provide the required voltage for the proper device operation. Implanting to form the source and drain regions is well within the level of ordinary skill in the art to precisely dope the regions to form the pn junction.

It would have been obvious to create contacts and implant as discussed above.

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Currie - US 6,831,292 describes making devices with strained layers.

Art Unit: 2891

Any inquiry concerning this communication or earlier communications from the examiner

should be directed to Chandra Chaudhari whose telephone number is 571-272-1688. The examiner

can normally be reached on Mon - Fri (9:00-5:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Bill

Baumeister can be reached on 571-272-1722. The fax phone number for the organization where this

application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained

from either Private PAIR or Public PAIR. Status information for unpublished applications is available

through Private PAIR only. For more information about the PAIR system, see http://pair-

direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the

Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Chandra Chaudhari

Primary Examiner

Art Unit 2891

Chandra Chaudhari

C. Chardhari

November 23, 2005